

## **Evaluation of AA-CVD Deposited Phase Pure Polymorphs of SnS for Thin Films Solar Cells**

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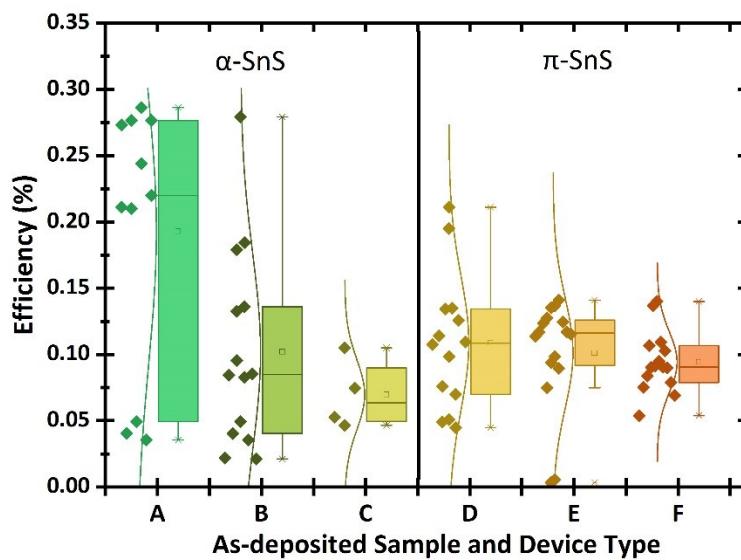
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## Supporting Information

**Table S1:** Summary of functional and shunted pixels per sample for as-deposited  $\alpha$ -SnS and  $\pi$ -SnS PV devices.

Device Structure	Treatment	No. of Shunted Pixels	Number of Rectifying Pixels
<b><math>\alpha</math>-SnS</b>			
A1: Mo/ $\alpha$ -SnS /CdS/i-ZnO/ITO	As completed	1	5
A2: Mo/ $\alpha$ -SnS /CdS/i-ZnO/ITO	As completed	15	6
B1: FTO/ $\alpha$ -SnS/CdS/i-ZnO/ITO	As completed	2	8
B2: FTO/ $\alpha$ -SnS/CdS/i-ZnO/ITO	As completed	10	6
C1: FTO/am-TiO <sub>x</sub> / $\alpha$ -SnS/CdS/i-ZnO/ITO	As completed	8	2
C2: FTO/am-TiO <sub>x</sub> / $\alpha$ -SnS/CdS/i-ZnO/ITO	As completed	11	2
<b><math>\pi</math>-SnS</b>			
D1: Mo/ $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	1	5
D2: Mo/ $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	11	9
E1: FTO/ $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	9	6
E2: FTO/ $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	0	10
F1: FTO/am-TiO <sub>x</sub> / $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	0	6
F2: FTO/am-TiO <sub>x</sub> / $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	9	9

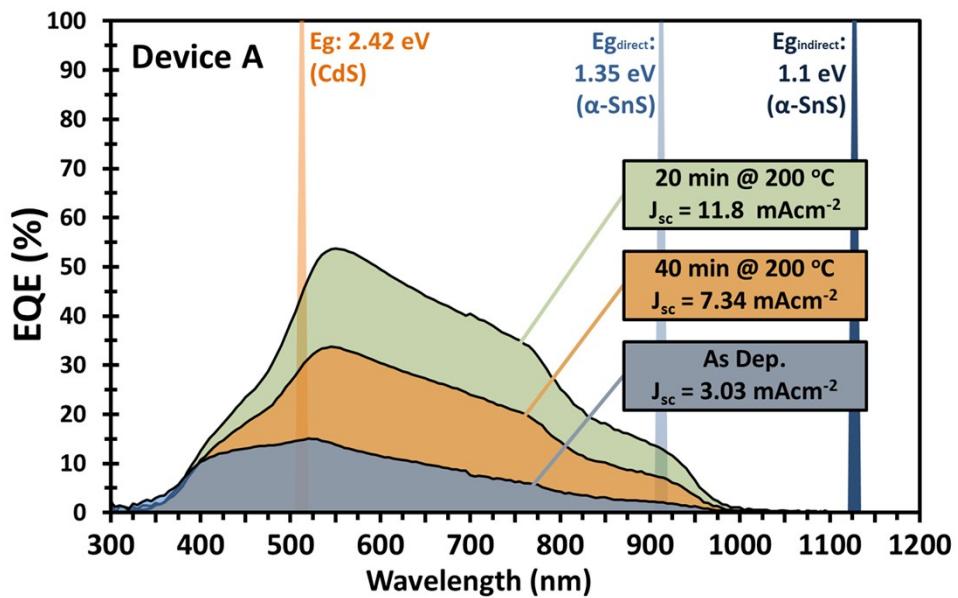


**Fig. S1** Statistical box plot for the distribution of solar conversion efficiencies for individual pixels within as-deposited samples consisting of device structures A, B, C, D, E, and F.

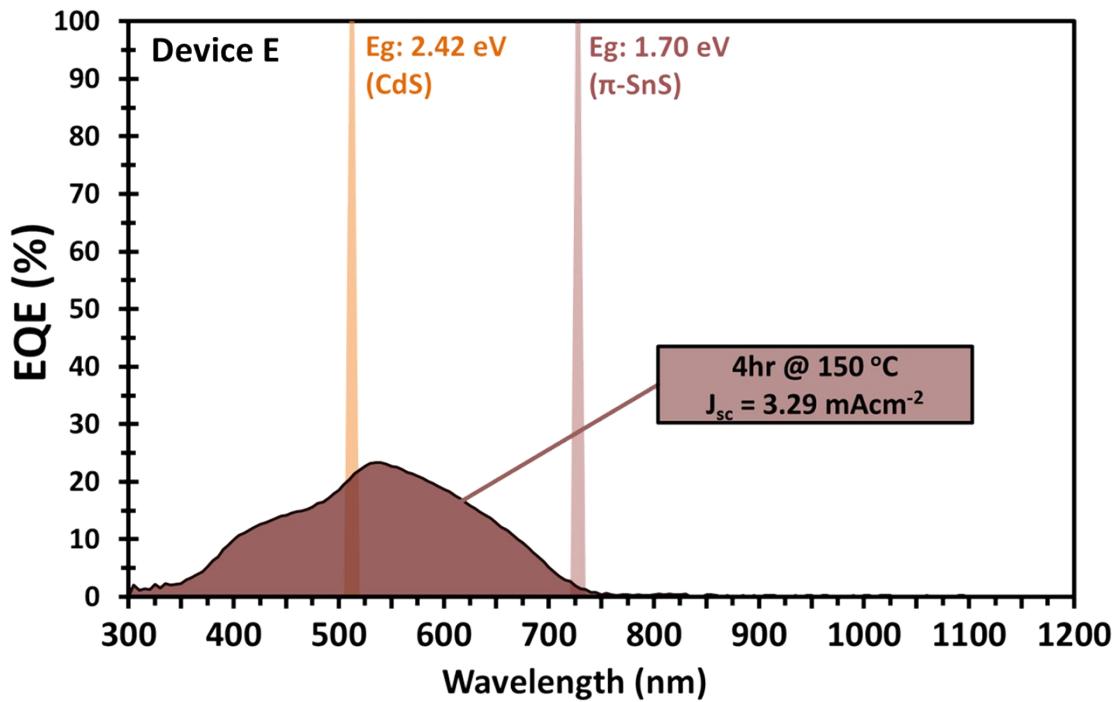
## Supporting Information

**Table S2:** Summary of all measured  $\alpha$ -SnS and  $\pi$ -SnS PV devices under an AM 1.5G illumination with different post fabrication hot plate annealing treatments.

Device Structure	Post Fabrication Hot Plate Annealing Method	$V_{OC}$ (mV)	$J_{SC}$ (mA cm $^{-2}$ )	FF (%)	Area (cm $^{-2}$ )	$\eta$ (%)
<b><math>\alpha</math>-SnS</b>						
A: Mo/ $\alpha$ -SnS /CdS/i-ZnO/ITO	As completed	170	3.81	45	0.1	0.29
<b>A: Mo/<math>\alpha</math>-SnS /CdS/i-ZnO/ITO</b>	<b>200 °C, 20 min</b>	<b>135</b>	<b>12.96</b>	<b>47</b>	<b>0.1</b>	<b>0.82</b>
A: Mo/ $\alpha$ -SnS /CdS/i-ZnO/ITO	200 °C, 40 min	100	8.01	43	0.1	0.35
B: FTO/ $\alpha$ -SnS/CdS/i-ZnO/ITO	As completed	160	4.26	40	0.1	0.28
<b>B: FTO/<math>\alpha</math>-SnS/CdS/i-ZnO/ITO</b>	<b>200 °C, 20 min</b>	<b>144</b>	<b>12.78</b>	<b>48</b>	<b>0.1</b>	<b>0.88</b>
B: FTO/ $\alpha$ -SnS/CdS/i-ZnO/ITO	200 °C, 40 min	95	7.91	43	0.1	0.32
<b>C: FTO/am-TiO<sub>x</sub>/<math>\alpha</math>-SnS/CdS/i-ZnO/ITO</b>	<b>As completed</b>	<b>85</b>	<b>3.74</b>	<b>31</b>	<b>0.1</b>	<b>0.1</b>
C: FTO/am-TiO <sub>x</sub> / $\alpha$ -SnS/CdS/i-ZnO/ITO	200 °C, 20 min	-	-	-	-	Shunted
C: FTO/am-TiO <sub>x</sub> / $\alpha$ -SnS/CdS/i-ZnO/ITO	200 °C, 40 min	-	-	-	-	Shunted
<b><math>\pi</math>-SnS</b>						
<b>D: Mo/<math>\pi</math>-SnS/CdS/i-ZnO/ITO</b>	<b>As completed</b>	<b>133</b>	<b>5.93</b>	<b>27</b>	<b>0.1</b>	<b>0.21</b>
D: Mo/ $\pi$ -SnS/CdS/i-ZnO/ITO	150 °C, 20 min	-	-	-	-	Shunted
E: FTO/ $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	180	2.00	40	0.1	0.14
E: FTO/ $\pi$ -SnS/CdS/i-ZnO/ITO	150 °C, 120 min	128	2.59	41	0.1	0.14
<b>E: FTO/<math>\pi</math>-SnS/CdS/i-ZnO/ITO</b>	<b>150 °C, 240 min</b>	<b>113</b>	<b>3.40</b>	<b>42</b>	<b>0.1</b>	<b>0.15</b>
F: FTO/am-TiO <sub>x</sub> / $\pi$ -SnS/CdS/i-ZnO/ITO	As completed	180	2.50	32	0.1	0.14
F: FTO/am-TiO <sub>x</sub> / $\pi$ -SnS/CdS/i-ZnO/ITO	150 °C, 120 min	200	3.50	31	0.1	0.22
<b>F: FTO/am-TiO<sub>x</sub>/<math>\pi</math>-SnS/CdS/i-ZnO/ITO</b>	<b>150 °C, 240 min</b>	<b>217</b>	<b>5.40</b>	<b>34</b>	<b>0.1</b>	<b>0.41</b>

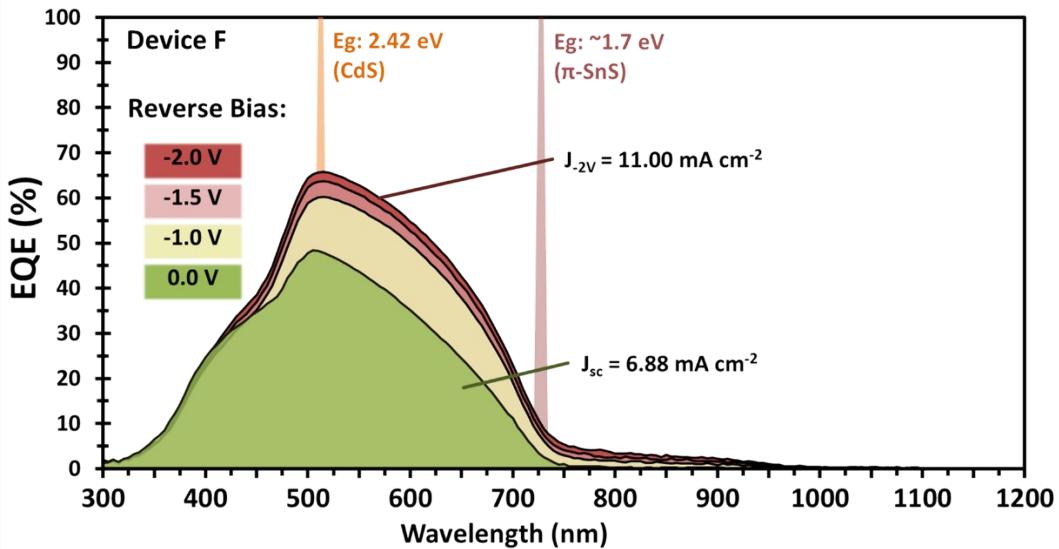


**Fig. S2** External quantum efficiency (EQE) vs photon wavelength for device A consisting of Mo/α-SnS/CdS/ZnO/ITO. The EQE measurements after consecutive hot plate annealing treatments are presented.

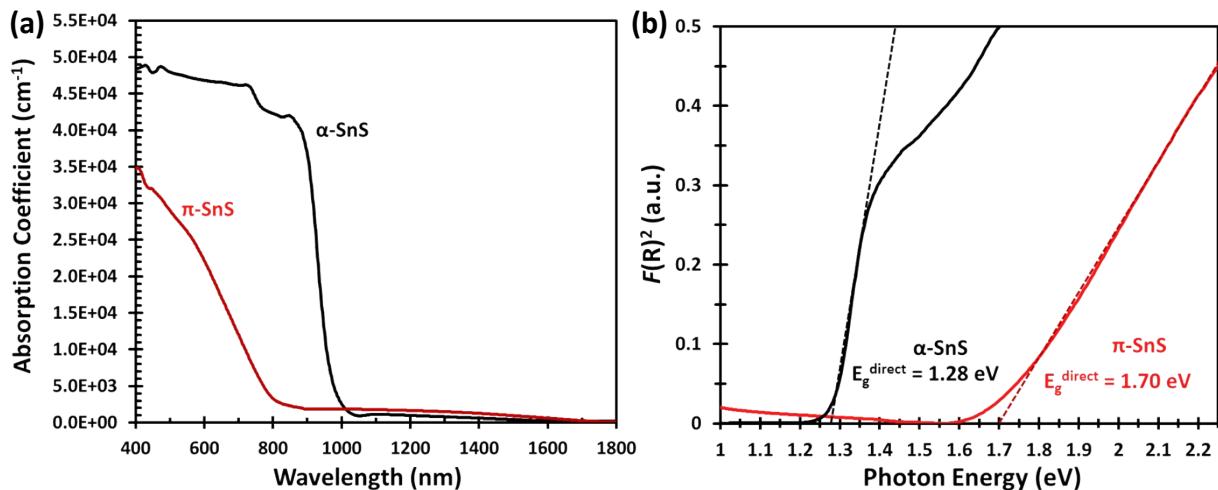


**Fig. S3** The EQE vs photon wavelength for Device E after hotplate annealing at 150 °C for 4 hours

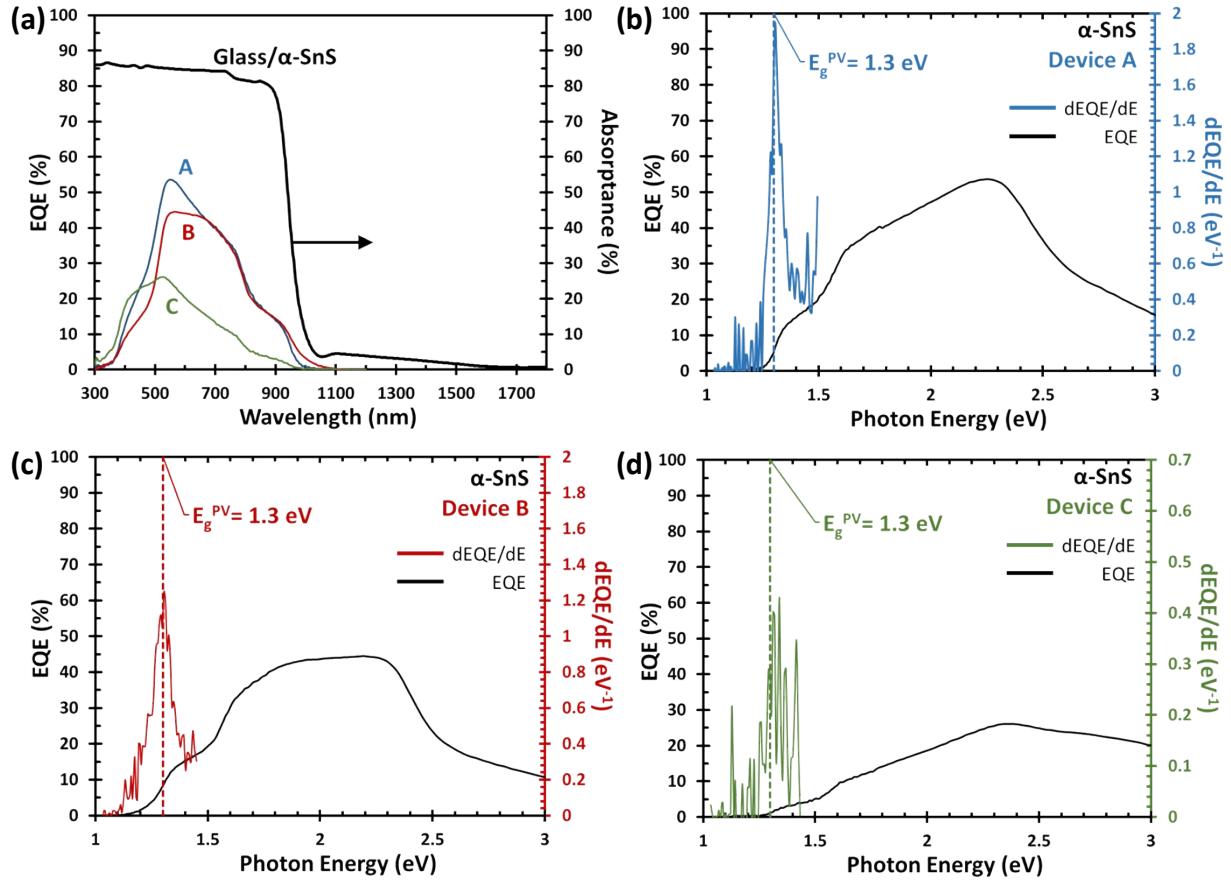
Supporting Information



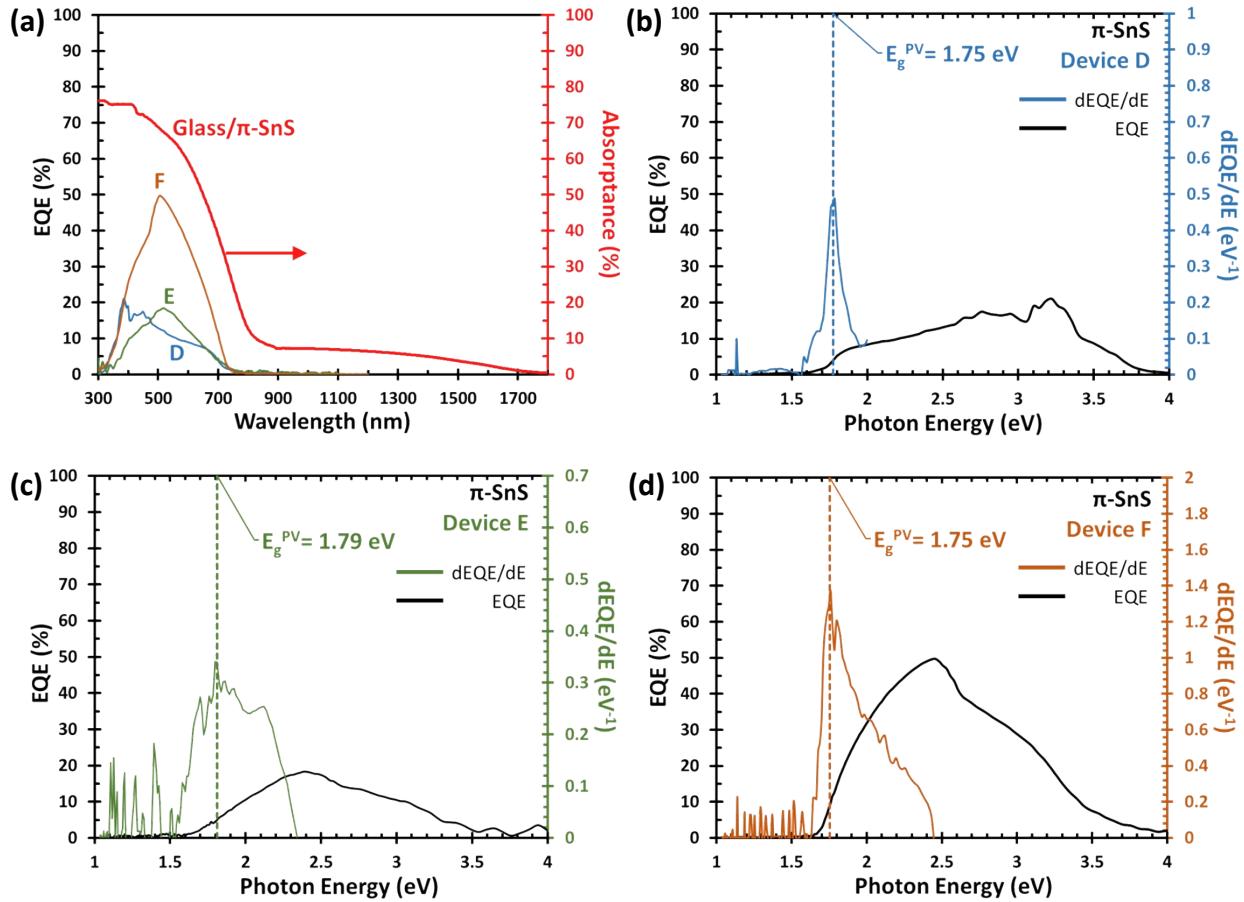
**Fig. S4** The EQE vs photon wavelength for Device F after hotplate annealing at 150 °C for 4 hours at different reverse bias potentials from 0 V to -2 V.



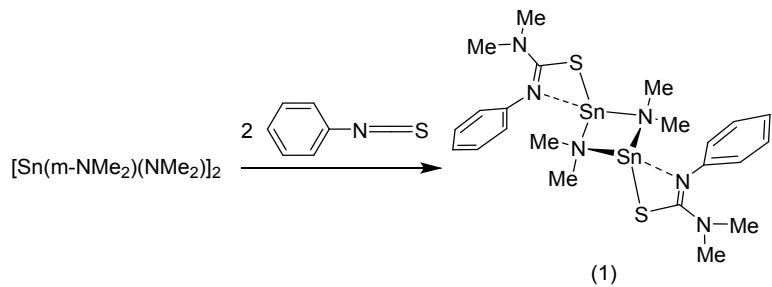
**Fig. S5** (a) absorption coefficient vs. wavelength and (b) Tauc plot of the Kubelka–Munck function for direct allowed transitions, determined from the UV-Vis-NIR transreflectance measurements for  $\alpha$ -SnS and  $\pi$ -SnS samples deposited on to glass.



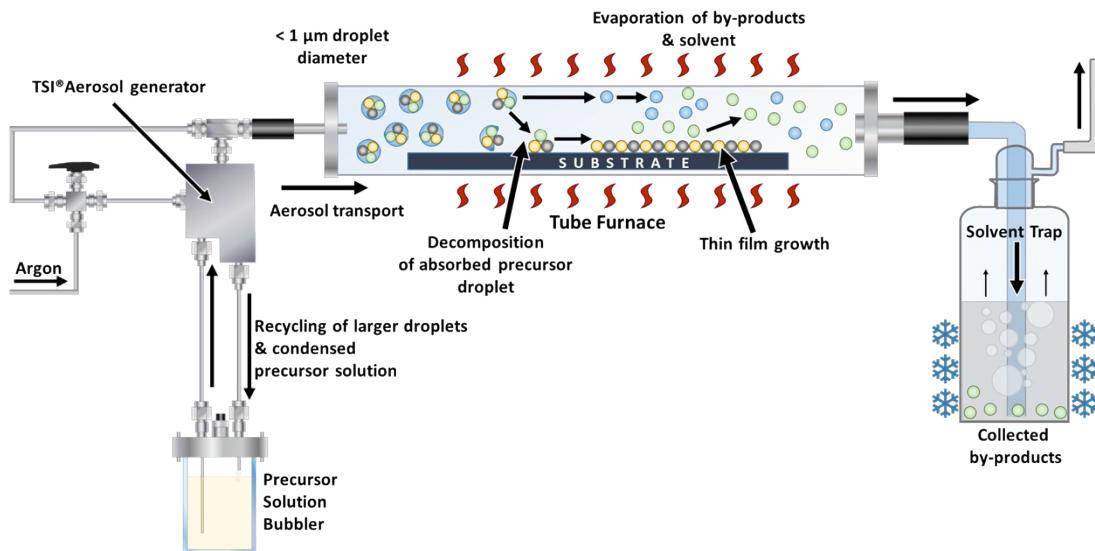
**Fig. S6** (a) Combined absorptance data for  $\alpha$ -SnS samples deposited onto glass (black) and the EQE data for optimized devices A (blue), B (red), and C (green) vs. wavelength. Measured EQE data (black) and its derivative (coloured) vs. photon energy, for devices consisting of  $\alpha$ -SnS, (b)A, (c)B, and (d)C. The photovoltaic (PV) band gap ( $E_g^{PV}$ ) is determined from the maximum point of the derivative,  $dEQE/dE$ .



**Fig. S7** (a) Combined absorptance data for  $\pi$ -SnS samples deposited onto glass (red) and the EQE data for optimized devices D (blue), E (green), and F (orange) vs. wavelength. Measured EQE data (black) and its derivative (coloured) vs. photon energy, for devices consisting of  $\pi$ -SnS, (b)D, (c)E, and (d)F. The photovoltaic (PV) band gap ( $E_g^{\text{PV}}$ ) is determined from the maximum point of the derivative,  $d\text{EQE}/dE$ .



**Scheme S1** Synthesis route to Dimethylamido-(N-Phenyl-N',N'-Dimethyl-Thiourate)Sn(II) dimer  $[\text{Sn}(\{\text{C}_6\text{H}_5\}\text{NCSN}\{\text{Me}_2\})(\text{NMe}_2)]$ , the Sn(II) thio-ureide single source precursor (1).<sup>1</sup>



**Fig. S8** Schematic of the aerosol assisted chemical vapor deposition (AA-CVD) apparatus used in this study. The aerosol was generated from a TSI® 3076 Aerosol generator.

#### References:

1. I. Y. Ahmet, M. S. Hill, A. L. Johnson and L. M. Peter, *Chemistry of Materials*, 2015, **27**, 7680-7688.